

Notice of References Cited	Application/Control No. 10/731,088	Applicant(s)/Patent Under Reexamination KAMIJIMA, AKIFUMI	
	Examiner Patricia A. George	Art Unit 1765	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2003/0143490	07-2003	Kozawa et al.	430/315
	B	US-2002/0187408	12-2002	Thackeray et al.	430/14
	C	US-6,916,597	07-2005	Kamijima et al.	430/314
	D	US-6,579,657	06-2003	Ishibashi et al.	430/270.1
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	JP 2001228616 A	08-2001	Japan	TANAKA et al.	G03F 07/095
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Abstract of Study for the design of high resolution novolak-DNQ photoresists: the effects of low-molecular-weight phenolic compounds on resist systems; Miyamoto et al.; July 1995; SPIE Vol. 2438, p. 223-234, Advances in Resist Technology and Processing XI
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.